

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("6846516").PN.	US-PGPUB; USPAT	OR	OFF	2008/06/09 20:06
L2	11706	silicon with precursor	US-PGPUB; USPAT	OR	ON	2008/06/09 20:11
L3	1011	2 and (precursor same (hydrogen and alkyls, halogen and cyclic))	US-PGPUB; USPAT	OR	ON	2008/06/09 20:11
L4	472	3 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/09 20:12
L5	78	((yoshihide with senzaki) or (sang with in with lee) or (sang with kyoo with lee)) and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/09 21:06
L6	3	(silicon near5 precursor) and 5	US-PGPUB; USPAT	OR	ON	2008/06/09 21:06
L7	75	5 not 6	US-PGPUB; USPAT	OR	ON	2008/06/09 21:07
S1	2	((("6030900") or ("20030040196"))).PN.	US-PGPUB; USPAT	OR	OFF	2007/09/14 15:55
S2	5	((("6203613") or ("6465371") or ("6869638") or ("7112539") or ("20030232511"))).PN.	US-PGPUB; USPAT	OR	OFF	2007/09/14 16:02
S3	4579	(silicon adj (oxide or dioxide)) and (organic with precursor)	US-PGPUB; USPAT	OR	ON	2007/09/14 16:51
S4	660	S3 and ozone	US-PGPUB; USPAT	OR	ON	2007/09/14 16:04
S5	459	S4 and (CVD or ALD)	US-PGPUB; USPAT	OR	ON	2007/09/14 16:46
S6	15	S5 and (precursor with (TMDSO or HMDSO or HMDSN or TEMAS))	US-PGPUB; USPAT	OR	ON	2007/09/14 16:23
S7	94	(silicon adj (oxide or dioxide)) and (organic with precursor)	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/14 16:24
S9	7	(silicon adj (oxide or dioxide)) and (organic with precursor) and ozone	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/14 16:45
S10	156	S4 and ALD	US-PGPUB; USPAT	OR	ON	2007/09/14 16:46
S11	7	S10 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2007/09/14 16:50
S12	1657	438/780,787,789,790.cds. and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2007/09/14 16:51

S13	1174	S12 and (silicon adj (oxide or dioxide))	US-PGPUB; USPAT	OR	ON	2007/09/14 16:52
S14	356	S13 and precursor	US-PGPUB; USPAT	OR	ON	2007/09/14 16:52
S15	5013	(silicon adj (oxide or dioxide)) and (organic with precursor)	US-PGPUB; USPAT	OR	ON	2008/06/07 17:26
S16	768	S15 and ozone	US-PGPUB; USPAT	OR	ON	2008/06/07 17:27
S17	207	S16 and ((atomic adj layer adj deposition) or ALD)	US-PGPUB; USPAT	OR	ON	2008/06/07 17:27
S18	12	S17 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 17:27
S19	12	S18 and temperature	US-PGPUB; USPAT	OR	ON	2008/06/07 17:27
S20	2514	ALD and oxynitride	US-PGPUB; USPAT	OR	ON	2008/06/07 20:05
S21	212	S20 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:05
S22	1	S21 and (nitrogen with simultaneously)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:05
S23	1	oxynitride and (nitrogen with simultaneously with ozone)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:07
S24	0	S23 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:07
S25	18	oxynitride and (nitrogen same simultaneously same ozone)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:07
S26	2	S25 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:07
S27	472	oxynitride and (nitrogen with ozone)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:11
S28	207	S27 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:11
S29	0	S28 and (silicon with organic with precursor) and purg\$3	US-PGPUB; USPAT	OR	ON	2008/06/07 20:11
S30	8	S28 and (silicon with precursor) and purg\$3	US-PGPUB; USPAT	OR	ON	2008/06/07 20:12
S31	60	S28 and silicon and purg\$3	US-PGPUB; USPAT	OR	ON	2008/06/07 20:15
S32	52	S31 not S30	US-PGPUB; USPAT	OR	ON	2008/06/07 20:16
S33	1	("20060178019").PN.	US-PGPUB; USPAT	OR	OFF	2008/06/07 20:29
S34	42	aviza near3 technology	US-PGPUB; USPAT	OR	ON	2008/06/07 20:29
S35	8	S34 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:29

S36	125	aviza near3 technology	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/07 20:30
S37	10	aviza near3 technology and oxynitride	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/07 20:30
S38	4	((("20030168750") or ("20020074584") or ("20010034097") or ("6551399")).PN.	US-PGPUB; USPAT	OR	OFF	2008/06/07 20:33
S39	1	S38 and oxynitride	US-PGPUB; USPAT	OR	ON	2008/06/07 20:33
S41	27	("without" with purg\$3) and ((forming or making) with oxynitride)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:35
S43	8	S41 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:36
S44	29	(silicon with organic with precursor) and ((forming or making) with oxynitride)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:42
S45	7	S44 and purg\$3	US-PGPUB; USPAT	OR	ON	2008/06/07 20:42
S46	295	(silicon with precursor) and ((forming or making) with oxynitride)	US-PGPUB; USPAT	OR	ON	2008/06/07 20:50
S47	143	S46 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 20:50
S48	29	S47 and ozone	US-PGPUB; USPAT	OR	ON	2008/06/07 20:50
S49	27	S47 and ozone and nitrogen	US-PGPUB; USPAT	OR	ON	2008/06/07 20:51
S50	2514	oxynitride and ALD	US-PGPUB; USPAT	OR	ON	2008/06/07 21:55
S51	212	S50 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/07 21:55
S52	28	S51 and nitrogen and silicon and ozone	US-PGPUB; USPAT	OR	ON	2008/06/07 21:55
S53	1	("20030040196").PN.	US-PGPUB; USPAT	OR	OFF	2008/06/07 22:58
S54	1	("6465044").PN.	US-PGPUB; USPAT	OR	OFF	2008/06/09 13:46
S55	1034	(oxygen near3 radical) with ozone	US-PGPUB; USPAT	OR	ON	2008/06/09 13:49
S56	455	S55 and @ad<"20020818"	US-PGPUB; USPAT	OR	ON	2008/06/09 13:50
S57	24	S56 and oxynitride	US-PGPUB; USPAT	OR	ON	2008/06/09 13:50

S58	3973	(forming or making) with oxynitride	US-PGPUB; USPAT	OR	ON	2008/06/09 14:00
S59	1790	S58 and @ad< "20020818"	US-PGPUB; USPAT	OR	ON	2008/06/09 14:00
S60	156	S59 and cvd and ozone	US-PGPUB; USPAT	OR	ON	2008/06/09 14:00
S61	26	S60 and (silicon with precursor)	US-PGPUB; USPAT	OR	ON	2008/06/09 14:01
S62	24	S61 and nitrogen	US-PGPUB; USPAT	OR	ON	2008/06/09 14:01

6/ 9/ 08 9:15:29 PM

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